

## Electronic Patent Application Fee Transmittal

<b>Application Number:</b>	10792038			
<b>Filing Date:</b>	03-Mar-2004			
<b>Title of Invention:</b>	Composition and process for post-etch removal of photoresist and/or sacrificial anti-reflective material deposited on a substrate			
<b>First Named Inventor/Applicant Name:</b>	Melissa K. Rath			
<b>Filer:</b>	Tristan Anne Fuierer/Lillian Glenn			
<b>Attorney Docket Number:</b>	ATMI-668			
Filed as Large Entity				
<b>Utility      Filing Fees</b>				
<b>Description</b>	<b>Fee Code</b>	<b>Quantity</b>	<b>Amount</b>	<b>Sub-Total in USD(\$)</b>
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
Post-Allowance-and-Post-Issuance:				
<b>Extension-of-Time:</b>				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Request for continued examination	1801	1	810	810
Total in USD (\$)				810